

PIEZOELECTRIC PLATEN DESIGN FOR IMPROVING PERFORMANCE IN CMP APPLICATIONS

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ABSTRACT OF THE DISCLOSURE

10 An invention is disclosed for improved performance in a CMP process using piezoelectric elements as a replacement for a platen air bearing. In one embodiment, a platen for improving performance in CMP applications is disclosed. The platen includes a plurality of piezoelectric elements disposed above the platen. In operation, the piezoelectric elements are used to exert force on the polishing belt during a CMP process. In this manner, zonal control is provided during the CMP process.